10/551553 JC12 Rec'd PCT/PTC 03 OCT 2005

Docket No.: 067161-0301 **PATENT**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :Customer Number: 20277

Toshihiko TANAKA :Confirmation Number: Not yet assigned

Application No.: Not yet assigned :Group Art Unit: Not yet assigned

Filed: October 03, 2005 :Examiner: Not yet assigned

For: SEMICONDUCTOR DEVICE FABRICATION METHOD AND MASK PATTERN

DATA GENERATION METHOD

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents and Trademarks Washington, D. C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed with the application and no certification or fee is required.

A copy of the foreign search report is attached for the Examiner's information. Please note this is a PCT application in the entry of the National Phase in the U.S. and copies of the references cited were transmitted by WIPO and are believed to be in the file of the above identified application and readily available to the Examiner. Therefore it is believed that Applicants have met all requirements regarding duty of disclosure under 37

10/551553

JC12 Rec'd PCT/PTC 03 OCT 2005

Not yet assigned

Acknowledgement and consideration of these documents are respectfully CFR 1.56.

requested.

A copy of the foreign search report is attached for the Examiner's information.

Please note this is a PCT application in the entry of the National Phase in the U.S.

However, to ensure that these references are available to the Examiner, we are providing

copies of these references herewith. Since the Search Report was from the U.S. JPO or EPO

search authorities, copies of these references should have been supplied to the USPTO under

the trilateral agreement and are believed to be in the file of the above identified application

and readily available to the Examiner.

Respectfully submitted,

McDERMOTT WILL & EMERY LLP

Please recognize our Customer No. 20277

as our correspondence address.

Stephen A. Becker

Registration No. 26,527

600 13th Street, N.W. Washington, DC 20005-3096

Phone: 202.756.8000 SAB:aph

Facsimile: 202.756.8087

Date: October 3, 2005

2

JC12 Rec'd PCT/PTC 03 OCT 2005

| *INFORMATION DISCLOSURE CITATION IN AN APPLICATION APPLICATION (PTO-1449) **CONSIDER ON TO STAND TO | · SHEEL _ OF _ | | | | | | | | | | | |
|--|--------------------------|--|---|---------------------------------------|-------------------------------------|--------------------------------|---|---|--------------------------|-------------------------------|----------|--|
| APPLICATION APPLICANT Toshihiko TANAKA FILING DATE October 03, 2005 U.S. PATENT DOCUMENTS EXAMINER'S INTIALS O. No. Number-Kind Codes of foreign of the state of the stat | 'INFC | | | 067161-0301 No | | | ot yet assigned | | | | | |
| (PTO-1449) Toshihiko TANAKA FILING DATE FILING DATE FILING DATE FILING DATE SUS. PATENT DOCUMENTS EXAMINER'S INTIALS OUS 0.5 (28,067 10-3-2000 Mashimoto Mashimoto | | | | | 1 | 0/5 | 5155 | 3 | | | | |
| U.S. PATENT DOCUMENTS EXAMINER'S INTIALS OF Section Patent Number (1998) US 0.128.067 10-3-2000 Hashimoto Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto Hashimoto US 0.128.067 10-3-2000 Hashimoto US 0.128.067 10-3-2 | | | | | | | | | | | | |
| EXAMINER'S INITIALS CITE No. Document Number Number (Number-Kind Codes praces) Publication Date MM-DD-YYYY Name of Patentee or Applicant of Cited Pages, Columns, Lines, Where Relevant Passages or Relevant | | O-1449) | | | | | | | | | | |
| No. Number-Kind Code; pt tensor) MM-DD-YYYY Document Relevant Passages or Relevant Figures Appear | U.S. PATENT DOCUMENTS | | | | | | | | | | | |
| No. Number-Kind Code; pi teneng MM-DD-YYYY Document Relevant Passages of Relevant Figures Appear | EXAMINER'S | INFR'S CITE Document Number Publication Date | | | | Name of Pater | Name of Patentee or Applicant of Cited Pages Columns Line | | | | es Where | |
| US | | | Nur | | | | | | | Relevant Passages or Relevant | | |
| US U | | | 11 | 6,128,067 | 10-3-2000 | | Hashimoto | | | | | |
| US U | | ļ | | | | | | | | | | |
| US | | | L | | | | | - | ļ | <u> </u> | | |
| US U | | | | | | | | | ļ | | | |
| US U | | ļ | | | | | | | <u> </u> | | | |
| EXAMINER'S INITIALS US US FOREIGN PATENT DOCUMENTS Publication Patenth Pages, Columns, Lines Translation Yes No EXAMINER'S CITE Country Codes, Number + Kind Codes (if known) Publication of Cited Document Figures Appear Yes No EXAMINER'S JP 6-275493 9-30-1994 Fujitsu Ltd. WiEnglish Abstract JP 5-90128 4-9-1993 Nikon Corp. WiEnglish Abstract JP 6-140306 5-20-1994 Nikon Corp. WiEnglish Abstract JP 8-203806 8-9-1996 Sony Corp. WiEnglish Abstract JP 6-67914 3-14-1989 Hitachi, Ltd. WiEnglish Abstract JP 2000-3028 1-7-2000 Toshiba Corp. WiEnglish Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. WiEnglish Abstract OTHER ART (Including Author, Title, Date, Perlinent Pages, Etc.) EXAMINER'S Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. 'Immersion Lithography Technology', NIKON Corp. retrieved February 19, 2004, via Internet | | | 1 1 | | | | | | | | | |
| EXAMINER'S INITIALS US US FOREIGN PATENT DOCUMENTS Foreign Patent Document Country Codes-Ambier - Kind Codes (if known) Foreign Patent Document Country Codes-Ambier - Kind Codes (if known) JP 6-275493 9-30-1994 Fujitsu Ltd. WEnglish Abstract JP 5-90128 4-9-1993 Nikon Corp. WEnglish Abstract JP 6-140306 5-20-1994 Nikon Corp. WEnglish Abstract JP 8-203806 8-9-1996 Sony Corp. WEnglish Abstract JP 2000-3028 1-7-2000 Toshiba Corp. WEnglish Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. WEnglish Abstract WEnglish Abstract WEnglish Abstract WEnglish Abstract WEnglish Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. WEnglish Abstract DTHER ART (including Author, Title, Date, Pertinent Pages, Etc.) Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, publisher, city and/or country where | | | | | | | | | <u> </u> | | | |
| EXAMINER'S INITIALS US | | | <u> </u> | | | | | | - | | | |
| EXAMINER'S INITIALS I Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. Tensistion Date Wienglish Abstract Abstract EXAMINER'S INITIALS I Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. Tensistion Date Wienglish Abstract Abstract EXAMINER'S Initials I Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. Tensistion Date Pages, Cloument Pages, Etc.) Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. Tensistion Date Pages, Cloument Pages, Etc.) Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, published. | | | L | | | | | | | | | |
| EXAMINER'S INITIALS INITIALS CITE NO. Foreign Patent Document Codes / Exempter - Kind Codes / | | | | · | | | | | | | | |
| INITIALS CITE NO. Country Codes Number 4 - Kind Codes (if known) JP 6-275493 9-30-1994 Fujitsu Ltd. W/English Abstract JP 5-90128 4-9-1993 Nikon Corp. W/English Abstract JP 6-140306 5-20-1994 Nikon Corp. W/English Abstract JP 8-203806 8-9-1996 Sony Corp. W/English Abstract JP 64-67914 3-14-1989 Hitachi, Ltd. W/English Abstract JP 2000-3028 1-7-2000 Toshiba Corp. W/English Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. W/English Abstract W/English Abstract W/English Abstract W/English Abstract W/English Abstract W/English Abstract DTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) EXAMINER'S INITIALS Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | FOREIGN PATENT DOCUMENTS | | | | | | | | | | | |
| NO. Codes (If known) JP 6-275493 | | | | | | Name of Patentee or Pages, Col | | | lumns, Lines Translation | | | |
| Abstract JP 5-90128 | INITIALS | | Codes (if known) | | | | | | | | No | |
| Abstract JP 6-140306 / 5-20-1994 Nikon Corp. | · | | | | | | | | | Abstract | | |
| Abstract JP 8-203806 8-9-1996 Sony Corp. W/English Abstract JP 64-67914 3-14-1989 Hitachi, Ltd. W/English Abstract JP 2000-3028 1-7-2000 Toshiba Corp. W/English Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. W/English Abstract OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) EXAMINER'S INITIALS CITE No. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, calalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | | 4-9-1993 | | | | | Abstract | | |
| Abstract JP 64-67914 3-14-1989 Hitachi, Ltd. W/English Abstract JP 2000-3028 1-7-2000 Toshiba Corp. W/English Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. W/English Abstract OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) EXAMINER'S INITIALS CITE NO. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | JP 6-140306 _/ | 5-20-1994 | Nikon Co | rp. | | | | | |
| Abstract JP 2000-3028 / 1-7-2000 Toshiba Corp. | | | | JP 8-203806 | 8-9-1996 | Sony Co | rp. | | | | | |
| Abstract JP 3-210560 8-13-1991 Fujitsu Ltd. W/English Abstract OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) EXAMINER'S INITIALS CITE NO. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. *Immersion Lithography Technology*, NIKON Corp. retrieved February 19, 2004, via Internet | | | | JP 64-67914 | 3-14-1989 | Hitachi, L | td. | | | | | |
| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) EXAMINER'S INITIALS CITE NO. "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | JP 2000-3028 / | 1-7-2000 | | | | | | | |
| EXAMINER'S INITIALS CITE NO. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | <u></u> | | | | | | | | |
| INITIALS CITE NO. journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | | | | | | | | | |
| | | CITE journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where | | | | | | | | | : | |
| EXAMINER DATE CONSIDERED | | | "Immersion Lithography Technology", NIKON Corp. retrieved February 19, 2004, via Internet | | | | | | | | 1 | |
| EXAMINER DATE CONSIDERED | | | | | | | | | | | + | |
| EXAMINER DATE CONSIDERED | | | 1 | · · · · · · · · · · · · · · · · · · · | | | | | | | 1 | |
| EXAMINER DATE CONSIDERED | | | | - | · · · · · · · · · · · · · · · · · · | | | | | | | |
| | | AMINER | | DATE CONSIDERED | | | | | | | | |

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.